L Number	Hits	Search Text	DB	Time stamp
34	5	("5189812"   "5325604"   "5458687"   "5609720"	USPAT	2003/07/29 10:50
		"5791895").PN.		
64	15	("4469529"   "5108792"   "5345534"   "5551985"   "5595606"	USPAT	2003/07/29 12:04
		"5624499"   "5650082"   "5683518"   "5708755"   "5711815"		
		"5846476"   "5889258"   "5900177"   "5937142"   "5970214").PN.		
65	106249	(adjust\$4 control\$4 var\$4 increas\$3 decreas\$3 lower\$3	USPAT;	2003/07/29 12:09
05	100249	rais\$3) near5 temperature near12 (antifreeze anti-freeze	US-PGPUB;	2000/07/20 12:00
İ		glycol ethyleneglycol water refrigerant ((((heat near2	EPO; JPO;	
		transfer\$4 near2 (fluid medium liquid gas vapor)) (heat near2	DERWENT;	
		exchang\$3 near2 (fluid medium liquid gas vapor))) (coolant	IBM_TDB	
		or (cooling near2 (fluid medium liquid gas vapor)))) (thermal		
		near2 transfer\$4 near2 (fluid medium liquid gas vapor))		
		(thermal near2 exchang\$3 near2 (fluid medium liquid gas		
	00470	vapor))))	LICDAT	2002/07/20 12:10
66	26170	(adjust\$4 control\$4 var\$4 increas\$3 decreas\$3 lower\$3 rais\$3) near12 (((flow\$3 circulat\$3 suppl\$4) near3 (rate	USPAT; US-PGPUB;	2003/07/29 12:10
		speed)) near8 (antifreeze anti-freeze glycol ethyleneglycol	EPO; JPO;	
		water refrigerant ((((heat near2 transfer\$4 near2 (fluid	DERWENT;	
		medium liquid gas vapor)) (heat near2 exchang\$3 near2	IBM_TDB	
		(fluid medium liquid gas vapor))) (coolant or (cooling near2	_	
		(fluid medium liquid gas vapor)))) (thermal near2 transfer\$4		
		near2 (fluid medium liquid gas vapor)) (thermal near2		
		exchang\$3 near2 (fluid medium liquid gas vapor)))))	LIODAT	0000/07/00 47:00
67	611	(adjust\$4 control\$4 var\$4 increas\$3 decreas\$3 lower\$3	USPAT; US-PGPUB;	2003/07/29 17:00
		rais\$3) near5 (power energy) near10 (process lamp ion electron) near10 (temperature near3 (wafer substrate	EPO; JPO;	
		workpiece plate susceptor pedestal support table chuck	DERWENT;	
		holder))	IBM_TDB	
69	18	((adjust\$4 control\$4 var\$4 increas\$3 decreas\$3 lower\$3	USPAT;	2003/07/29 12:14
		rais\$3) near12 (((flow\$3 circulat\$3 suppl\$4) near3 (rate	US-PGPUB;	
		speed)) near8 (antifreeze anti-freeze glycol ethyleneglycol	EPO; JPO;	
		water refrigerant ((((heat near2 transfer\$4 near2 (fluid	DERWENT;	
		medium liquid gas vapor)) (heat near2 exchang\$3 near2	IBM_TDB	
		(fluid medium liquid gas vapor))) (coolant or (cooling near2		
		(fluid medium liquid gas vapor)))) (thermal near2 transfer\$4 near2 (fluid medium liquid gas vapor)) (thermal near2		
		exchang\$3 near2 (fluid medium liquid gas vapor))))) ) and		
		((adjust\$4 control\$4 var\$4 increas\$3 decreas\$3 lower\$3		
		rais\$3) near5 (power energy) near10 (process lamp ion		
		electron) near10 (temperature near3 (wafer substrate		
		workpiece plate susceptor pedestal support table chuck		
		holder)))		
70	41	5200023.URPN.	USPAT	2003/07/29 12:16
71	9	("3664942"   "3718757"   "4396478"   "4675072"   "4883560"     "4913790"   "4919542"   "4936967"   "4971653").PN.	USPAT	2003/07/29 12:46
72	11	4396478.URPN.	USPAT	2003/07/29 12:55
73	18	("4184480"   "4409511"   "4427378"   "4680447"   "4920918"	USPAT	2003/07/29 13:15
, ,	,	"4945251"   "5145716"   "5152060"   "5743643"   "5762713"		
		"5781693"   "5790751"   "5863334"   "5960158"   "6143079"		
		"6148761"   "6284051"   "6435869").PN.		
68	68	((adjust\$4 control\$4 var\$4 increas\$3 decreas\$3 lower\$3	USPAT;	2003/07/29 14:42
		rais\$3) near5 temperature near12 (antifreeze anti-freeze	US-PGPUB;	
		glycol ethyleneglycol water refrigerant ((((heat near2	EPO; JPO;	
		transfer\$4 near2 (fluid medium liquid gas vapor)) (heat near2 exchang\$3 near2 (fluid medium liquid gas vapor))) (coolant	DERWENT;	
		or (cooling near2 (fluid medium liquid gas vapor))) (coolant	I IOIVI_ I DB	
		near2 transfer\$4 near2 (fluid medium liquid gas vapor)))		
		(thermal near2 exchang\$3 near2 (fluid medium liquid gas		
		vapor))))) and ((adjust\$4 control\$4 var\$4 increas\$3		
		decreas\$3 lower\$3 rais\$3) near5 (power energy) near10		
		(process lamp ion electron) near10 (temperature near3		
		(wafer substrate workpiece plate susceptor pedestal support		
1		table chuck holder)))		

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74	55	(((adjust\$4 control\$4 var\$4 increas\$3 decreas\$3 lower\$3	USPAT;	2003/07/29 16:58
		rais\$3) near5 temperature near12 (antifreeze anti-freeze	US-PGPUB;	
		glycol ethyleneglycol water refrigerant ((((heat near2	EPO; JPO;	
		transfer\$4 near2 (fluid medium liquid gas vapor)) (heat near2	DERWENT,	
	İ	exchang\$3 near2 (fluid medium liquid gas vapor))) (coolant	IBM_TDB	
		or (cooling near2 (fluid medium liquid gas vapor)))) (thermal	_	
		near2 transfer\$4 near2 (fluid medium liquid gas vapor))		
		(thermal near2 exchang\$3 near2 (fluid medium liquid gas		
		vapor)))) ) and ((adjust\$4 control\$4 var\$4 increas\$3		
		decreas\$3 lower\$3 rais\$3) near5 (power energy) near10		
		(process lamp ion electron) near10 (temperature near3		
		(wafer substrate workpiece plate susceptor pedestal support		
		table chuck holder)))) not (((adjust\$4 control\$4 var\$4		
		increas\$3 decreas\$3 lower\$3 rais\$3) near12 (((flow\$3		
		circulat\$3 suppl\$4) near3 (rate speed)) near8 (antifreeze		
		anti-freeze glycol ethyleneglycol water refrigerant ((((heat		
		near2 transfer\$4 near2 (fluid medium liquid gas vapor)) (heat		
		near2 exchang\$3 near2 (fluid medium liquid gas vapor)))		
		(coolant or (cooling near2 (fluid medium liquid gas vapor))))		
		(thermal near2 transfer\$4 near2 (fluid medium liquid gas		
		vapor)) (thermal near2 exchang\$3 near2 (fluid medium liquid		
		gas vapor))))))) and ((adjust\$4 control\$4 var\$4 increas\$3		
		decreas\$3 lower\$3 rais\$3) near5 (power energy) near10		
		(process lamp ion electron) near10 (temperature near3		
		(wafer substrate workpiece plate susceptor pedestal support		
		table chuck holder))))		
75	13	5605600.URPN.	USPAT	2003/07/29 16:27
76	13	5605600.URPN.	USPAT	2003/07/29 16:27
77	19	("4261762"   "4457359"   "4508161"   "4533430"   "4855017"	USPAT	2003/07/29 16:27
• •		"4903754"   "4949783"   "4963713"   "5001423"   "5093579"		
		"5155331"   "5191218"   "5203958"   "5267607"   "5270266"		
		"5290381"   "5320982"   "5366002"   "5458734").PN.		
78	1582	((control\$4 adjust\$4) near3 temperature near10 (wafer	USPAT;	2003/07/29 17:00
		substrate workpiece plate susceptor pedestal support table	US-PGPUB;	
		chuck holder)).ti.	EPO; JPO;	
		<i>"</i>	DERWENT;	
			IBM_TDB	
79	1017	(((control\$4 adjust\$4) near3 temperature near10 (wafer	USPAT;	2003/07/29 17:21
		substrate workpiece plate susceptor pedestal support table	US-PGPUB;	
		chuck holder)).ti.) and (VLSI ULSI semiconductor wafer	EPO; JPO;	
		substrate (integrated adj circuit))	DERWENT;	
			IBM_TDB	
80	18	((adjust\$4 control\$4 var\$4 increas\$3 decreas\$3 lower\$3	USPAT;	2003/07/29 17:21
		rais\$3) near5 (power energy) near10 (process lamp ion	US-PGPUB;	
		electron) near10 (temperature near3 (wafer substrate	EPO; JPO;	
		workpiece plate susceptor pedestal support table chuck	DERWENT;	
		holder))) and ((((control\$4 adjust\$4) near3 temperature	IBM_TDB	
		near10 (wafer substrate workpiece plate susceptor pedestal		
		support table chuck holder)).ti.) and (VLSI ULSI		
		semiconductor wafer substrate (integrated adj circuit)))		1